

IN THE CLAIMS

Please amend the claims as follows.

1. (Currently Amended) A system for photoresist recovery comprising:
a nozzle to dispense a photoresist;
a bowl having an interior region and an interior surface;
a wafer platform disposed within the interior region of the bowl;
a wafer spindle coupled to the wafer platform, the wafer spindle ~~capable of spinning~~
to spin the wafer platform ~~such that~~ to propel an excess amount of a photoresist deposited
upon a wafer placed upon the wafer platform ~~is propelled~~ to the interior surface of the bowl;
and
a photoresist recovery container; and
a perimeter drain formed within the bowl such that the excess amount of photoresist
propelled from the wafer proceeds through the perimeter drain to a the photoresist recovery
container.
2. (Original) The system of claim 1 wherein the photoresist recovery container is
coupled to the bowl via a recovery drainpipe.
3. (Original) The system of claim 2 further comprising:
a recovery drainpipe block capable of being positioned in front of the recovery
drainpipe to prevent contaminants from entering the recovery drainpipe.

4. (Currently Amended) The system of claim 1 wherein the perimeter drain is formed level with a wafer rotation position within the interior surface of the bowl ~~level with a wafer rotation position.~~

5. (Currently Amended) The system of claim 1 further comprising a solvent vapor supply means coupled to the recovery drainpipe to provide ~~wherein~~ a solvent-rich environment ~~is maintained~~ within the recovery drainpipe.

6. (Cancelled)

7. (Cancelled)

8. (Original) The system of claim 1 further comprising:
one or more additional perimeter drains formed within the bowl to recover one or more additional types of photoresists in corresponding photoresist recovery containers.

9-27 (Cancelled)